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PATENT

THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the application of)

Bright et al.)

Application No. 10/722,839)

Filed: November 25, 2003)

For: APPARATUS FOR CONTROLLING)
WAFA TEMPERATURE IN CHEMICAL)
MECHANICAL POLISHING)

Examiner: G.B.M. Nguyen

Group Art Unit: 3723

Docket No: LAM2P318D

Date: March 21, 2005

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on March 21, 2005.

Signed: _____

Ray Harlow

REQUEST FOR CORRECTED FILING RECEIPT

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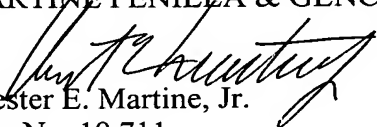
Sir:

Enclosed is a copy of the Filing Receipt for the above-identified patent application. Please reprint the Filing Receipt as follows and mail the corrected copy to the undersigned.

Please change the title from "Apparatus methods for controlling wafer temperature in chemical mechanical polishing " to – Apparatus for controlling wafer temperature in chemical mechanical polishing --.

The Commissioner is authorized to charge any fees that may be due to Deposit Account 50-0805 (Order No. LAM2P318D).

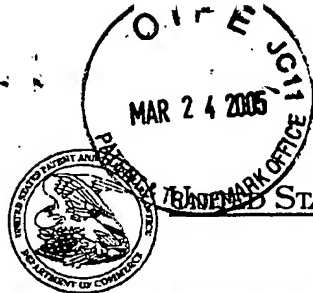
Respectfully submitted,
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APPL NO.	FILING OR 371 (c) DATE	ART UNIT	FIL FEE REC'D	ATTY. DOCKET NO	DRAWINGS	TOT CLMS	IND CLMS
10/722,839	11/25/2003	3723	770	LAM2P318D	9	15	3

CONFIRMATION NO. 8198

25920
 MARTINE & PENILLA, LLP
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FILING RECEIPT



OC000000012012119

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Receipt is acknowledged of this regular Patent Application. It will be considered in its order and you will be notified as to the results of the examination. Be sure to provide the U.S. APPLICATION NUMBER, FILING DATE, NAME OF APPLICANT, and TITLE OF INVENTION when inquiring about this application. Fees transmitted by check or draft are subject to collection. Please verify the accuracy of the data presented on this receipt. If an error is noted on this Filing Receipt, please write to the Office of Initial Patent Examination's Filing Receipt Corrections, facsimile number 703-746-9195. Please provide a copy of this Filing Receipt with the changes noted thereon. If you received a "Notice to File Missing Parts" for this application, please submit any corrections to this Filing Receipt with your reply to the Notice. When the USPTO processes the reply to the Notice, the USPTO will generate another Filing Receipt incorporating the requested corrections (if appropriate).

Applicant(s)

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Assignment For Published Patent Application

LAM Research Corporation;

Domestic Priority data as claimed by applicant

This application is a DIV of 10/033,455 12/26/2001

Foreign Applications

If Required, Foreign Filing License Granted: 03/01/2004

Projected Publication Date: 06/10/2004

Non-Publication Request: No

Early Publication Request: No

Title

Apparatus-methods for controlling wafer temperature in chemical mechanical polishing

Preliminary Class

438

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